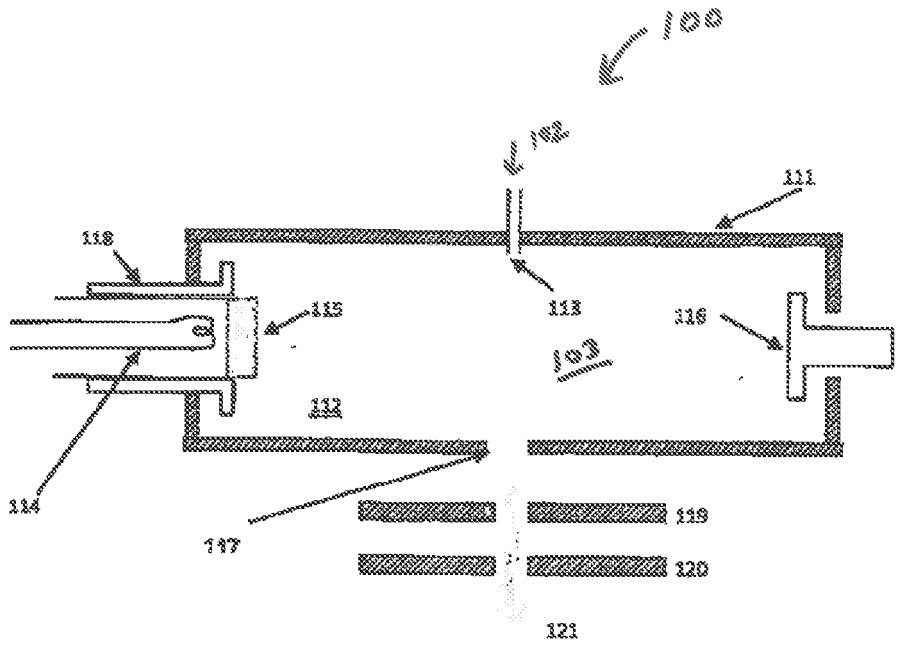
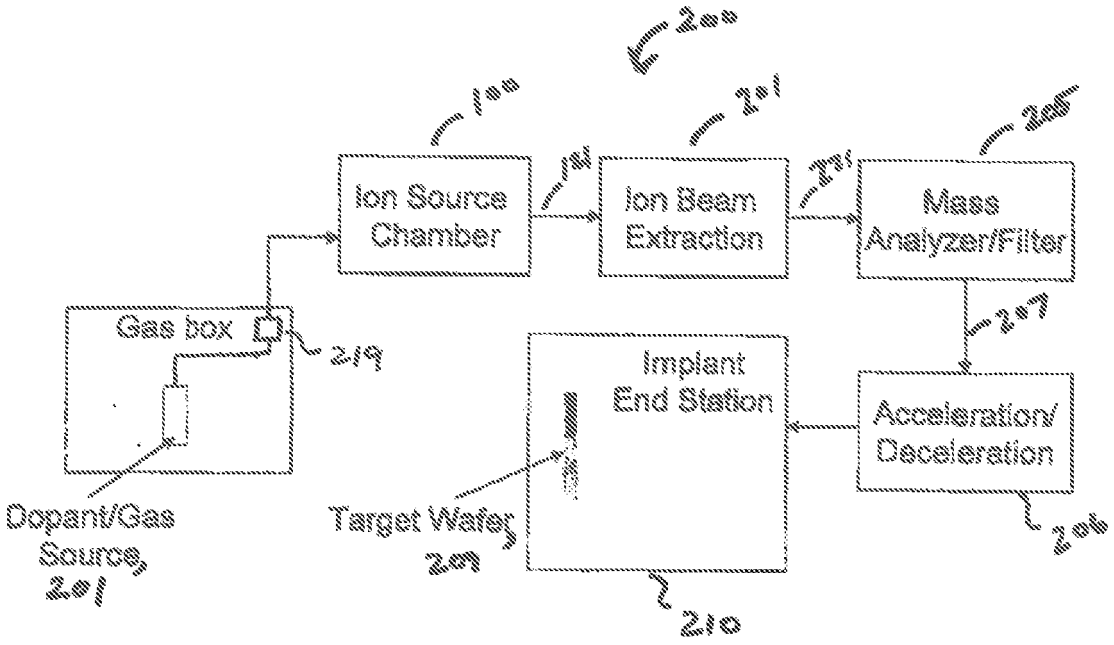


Schematic of an ion source apparatus

FIG. 1

FIG. 2


200
100
101
205
Ion Source Chamber
Ion Beam Extraction
Mass Analyzer/Filter
207
Gas box
219
Implant End Station
Acceleration/ Deceleration
206
Dopant/Gas Source 201
Target Wafer 209
210

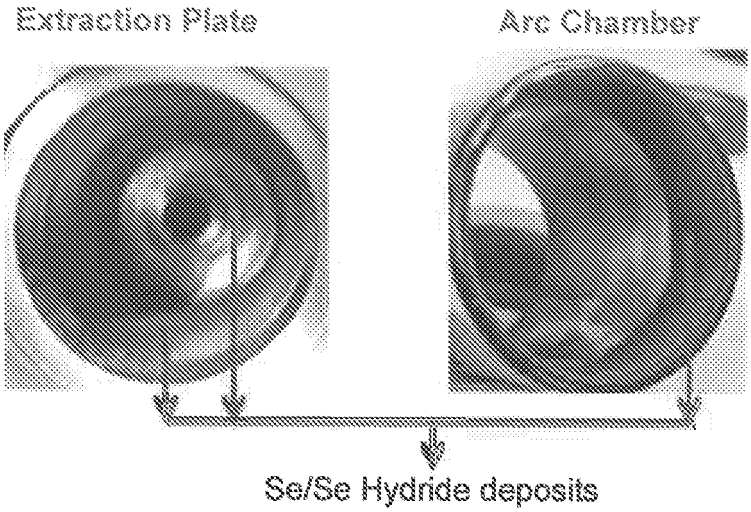


Figure 3a and 3b: Deposits during H_2Se Implant

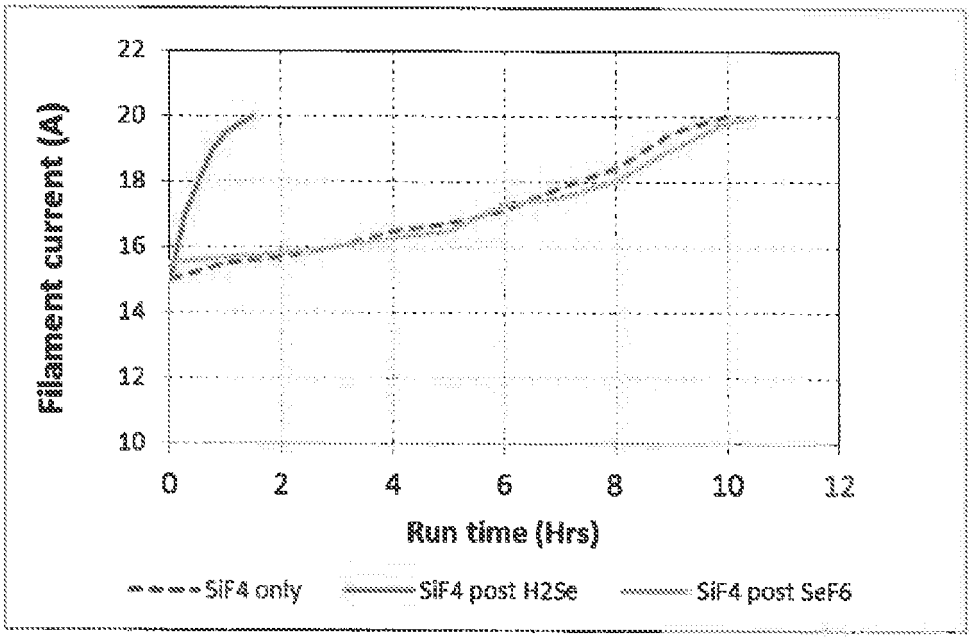
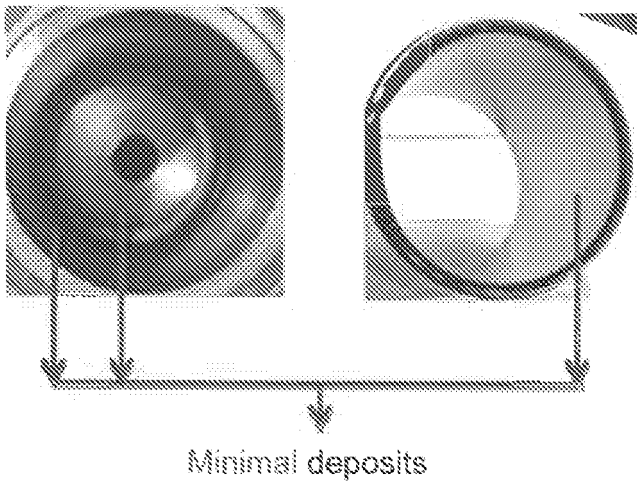


Figure 4: Filament current trend during SiF4 implant

Figures 5a and 5b: Deposits during enriched SeF_6 implant